

ABSTRACT

An object of the invention is to provide a method for manufacturing a polishing pad that has a high level of optical detection accuracy and is prevented from causing slurry leak from between the polishing region and the light-transmitting region. The invention is directed to a method for manufacturing a polishing pad, including the steps of: preparing a cell-dispersed urethane composition by a mechanical foaming method; placing a light-transmitting region at a predetermined position on a face material or a belt conveyor, while feeding or moving the face material or the belt conveyor; continuously discharging the cell-dispersed urethane composition onto a part of the face material or the belt conveyor where the light-transmitting region is not placed; placing another face material or belt conveyor on the discharged cell-dispersed urethane composition; curing the cell-dispersed urethane composition to form a polishing region including a polyurethane foam, while its thickness is controlled to be uniform, so that a polishing sheet is prepared; applying a polyurethane resin coating composition containing an aliphatic and/or alicyclic polyisocyanate to one side of the polishing sheet and curing the polyurethane resin coating composition to form a water-impermeable film; and

cutting the polishing sheet.